

# P and N-type doping of single crystal CdTe, CdSeTe

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## Major Considerations

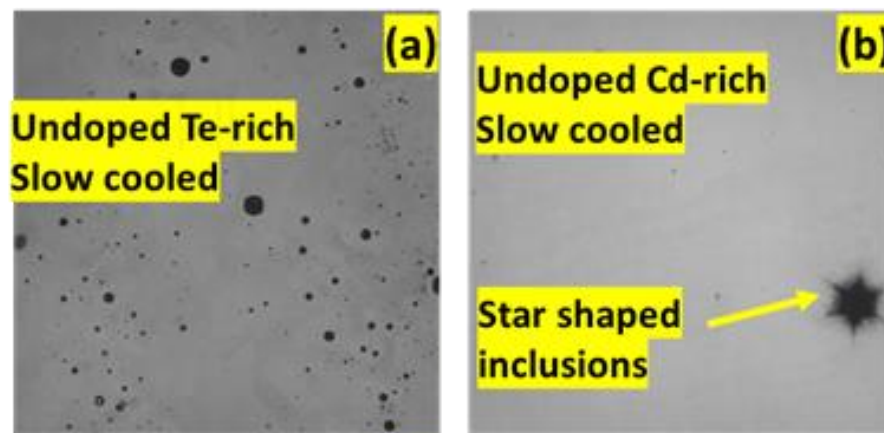
- Dopant solubility, stoichiometry condition
- Depth from band edges (20-100 meV)
  - P-type:  $\text{Na}_{\text{Cd}}$ ,  $\text{P}_{\text{Te}}$ ,  $\text{As}_{\text{Te}}$
  - N-Type:  $\text{In}_{\text{Cd}}$ ,  $\text{Al}_{\text{Cd}}$ ,  $\text{Cl}_{\text{Te}}$ ,  $\text{I}_{\text{Te}}$
- Compensation: Native defects, complexes, unintentional impurities, AX or DX centers
- Stability

# Doping in melt growth, stoichiometry, secondary phases



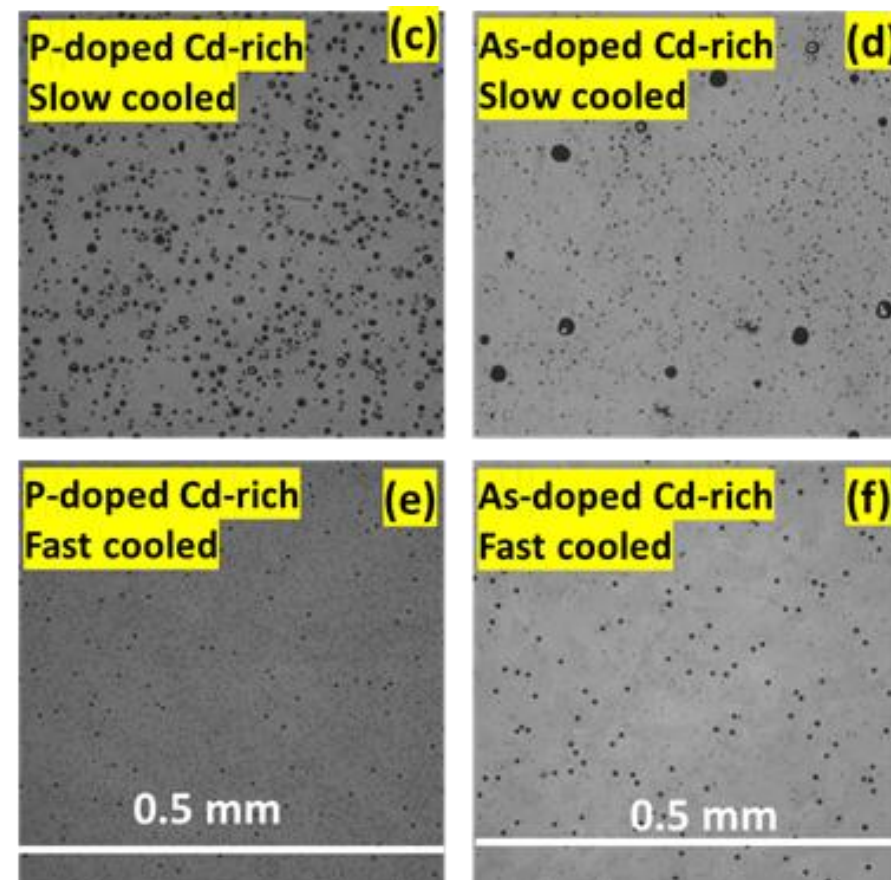
Melt grown crystals

Undoped



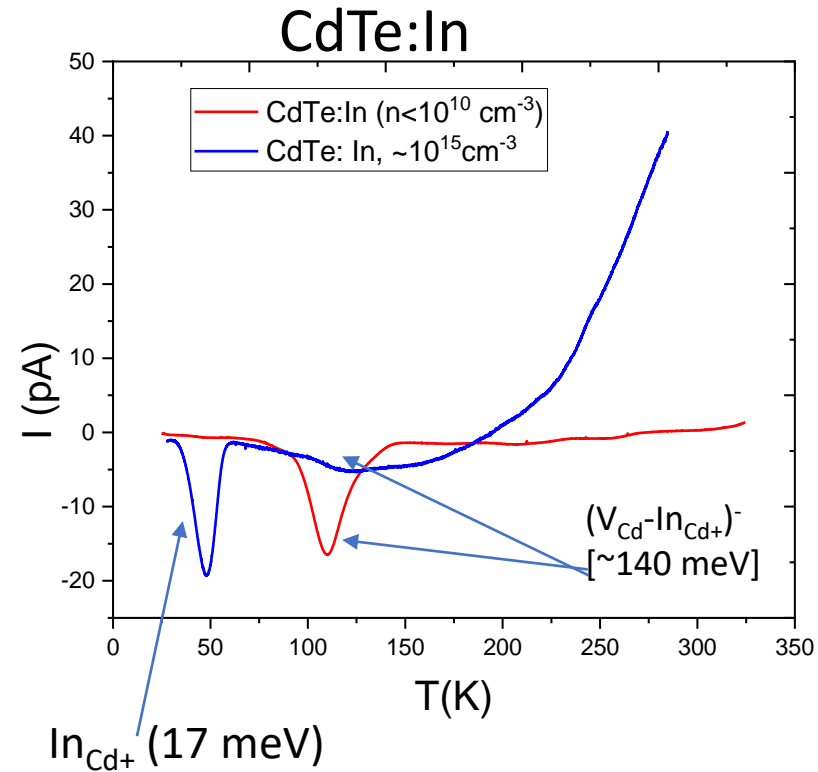
IR micrographs

P and As doped



# Compensating defects, A-center self compensation

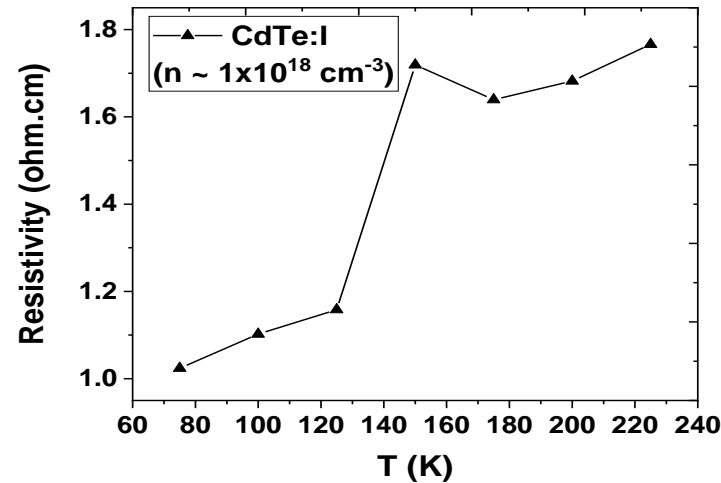
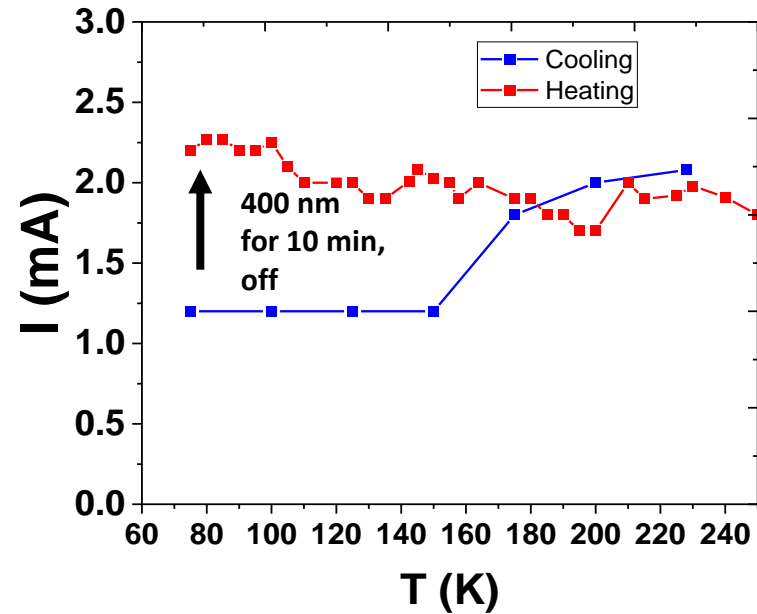
- Affects n-type doping by forming acceptor complexes with Cd vacancies
- Cd-annealing makes more n-type, for both site donors.



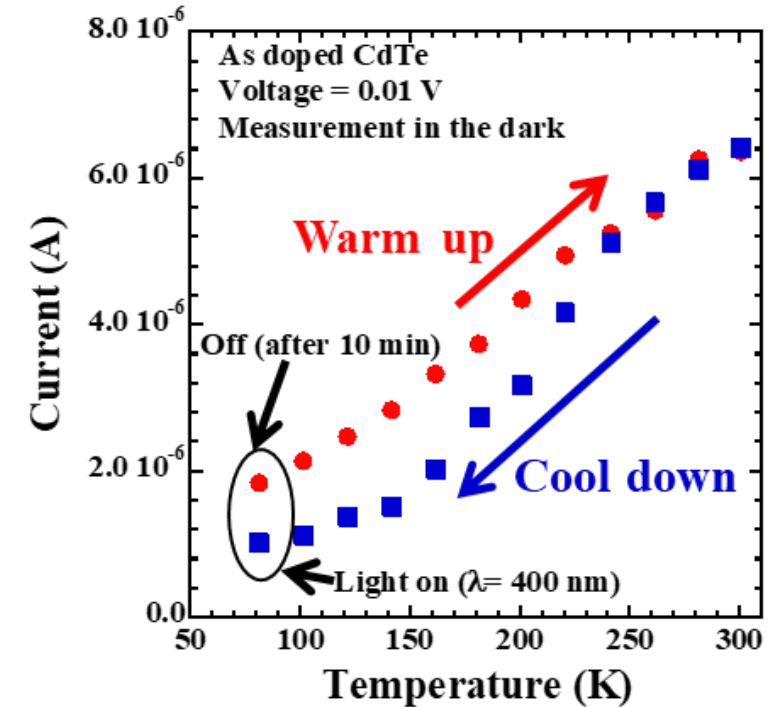
Thermoelectric spectroscopy on CdTe:In

# Compensating defects, AX, DX center

Iodine doping showing persistent current,  
 $n \sim 10^{18} \text{cm}^{-3}$

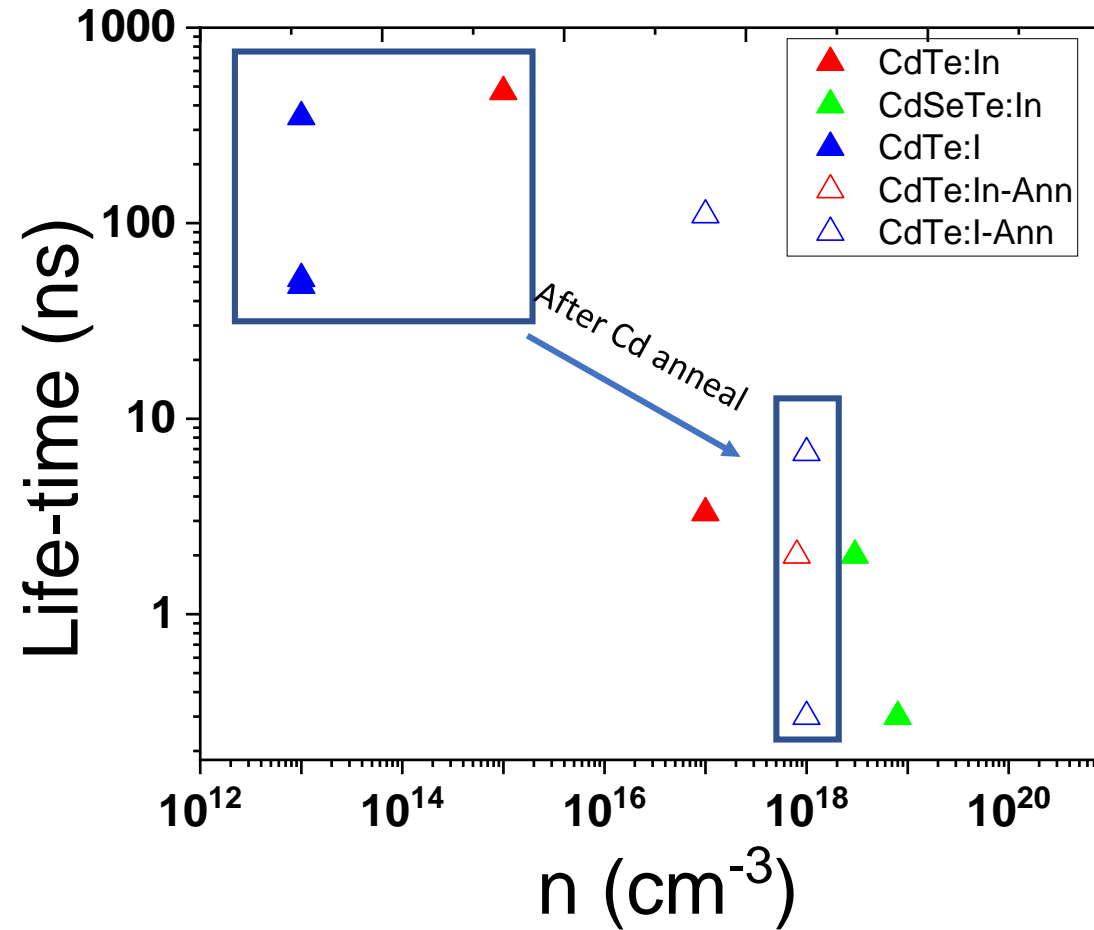


Arsenic AX center



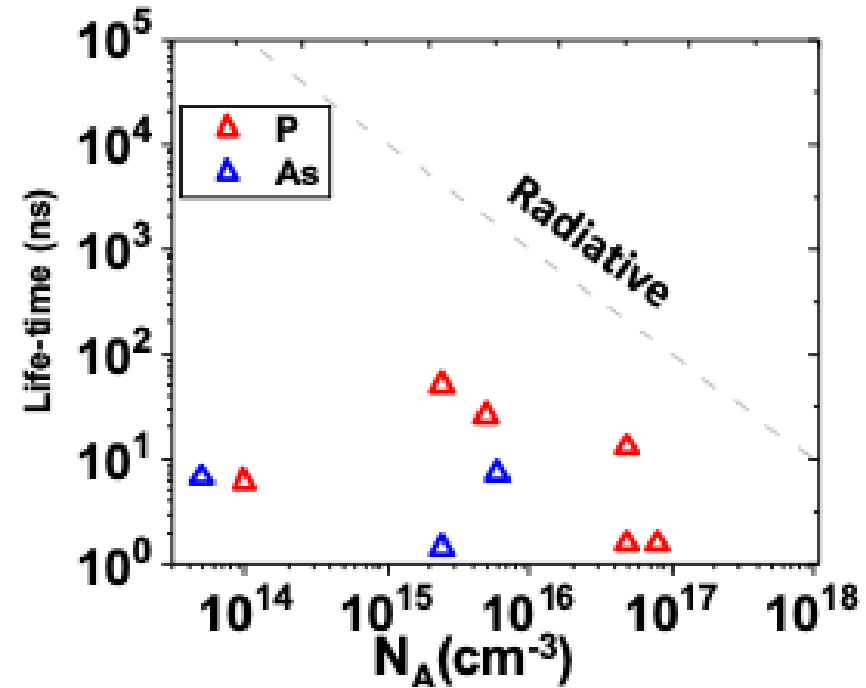
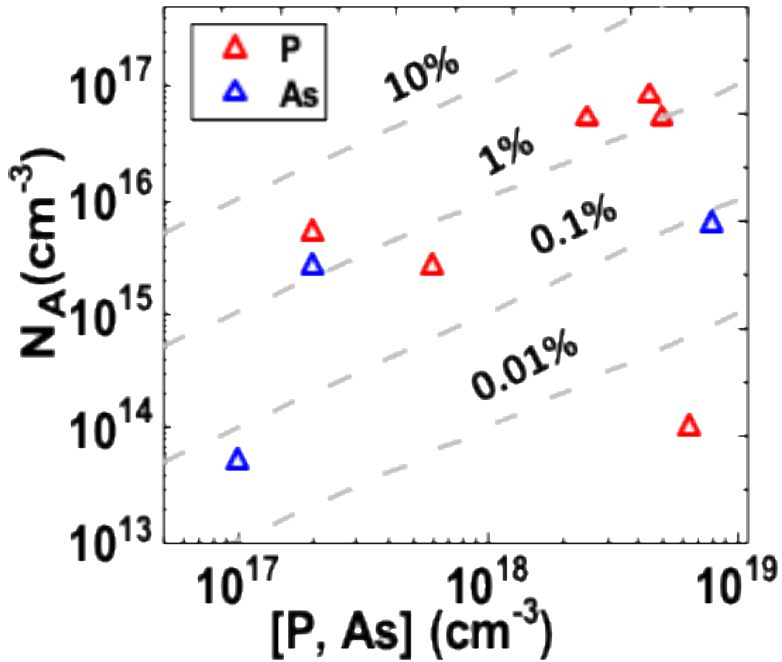
Nagaoka et. Al, Appl. Phys. Lett. **111**, 232103 (2017)

# N-type doping summary



For n-type dopants in CdTe,  $n > 10^{18} \text{ cm}^{-3}$  is easily achievable, after Cd annealing, where as CdSeTe does not seem to require any anneals.

# P-type doping summary



Hole density and life-time has been relatively inferior for As doping compared to P,

Growth methods incorporates melt convection showed better lifetime and doping efficiency, and could be attempted for other CdTe alloys including CdSeTe, in combination with Cd flux.